

Docket No.: 50212-211



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Kenichi ARIMURA, et al.

Serial No.: 09/807,902

Filed: April 19, 2001

Group Art Unit: 1763

Examiner: R. Bueker

For: WAFER SUPPORT IN SEMICONDUCTOR PRODUCTION APPARATUS

AMENDMENT

Commissioner for Patents  
Washington, DC 20231

Sir:

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**RECEIVED**  
MAR 06 2002  
**TC 1700**

The following amendment and remarks are submitted in response to the Office

Action dated November 30, 2001.

IN THE CLAIMS

The claims are amended as follows:

1. A semiconductor production apparatus including a process chamber; a wafer support disposed within said process chamber for supporting a semiconductor wafer; and a heating source for heat treatment of the semiconductor wafer supported by said wafer support;

wherein said wafer support comprises a susceptor having an upper surface for mounting said semiconductor wafer thereon, and a susceptor support shaft for supporting said susceptor from thereunder; wherein said susceptor support shaft having a main shaft positioned substantially coaxial with a center of said susceptor, and at least three arms radially extending from an upper end of said main shaft, each said arm having a distal

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